

Title (en)

SPUTTER TARGET WITH SPUTTER MATERIAL BASED ON TIO₂, AND A PRODUCTION METHOD

Title (de)

SPUTTERTARGET MIT EINEM SPUTTERMATERIAL AUF BASIS TIO₂ SOWIE HERSTELLVERFAHREN

Title (fr)

CIBLE DE PULVÉRISATION AVEC UN MATÉRIAU DE PULVÉRISATION À BASE DE TIO₂ AINSI QUE PROCÉDÉ DE FABRICATION

Publication

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Application

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Priority

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- DE 102006027029 A 20060609

Abstract (en)

[origin: WO2007141003A1] The invention relates to a sputter target, with sputter material based on TiO₂ which has 15-60 mol % of Nb₂O₅. The invention further relates to a method for the production of a sputter target consisting of the following steps: - mixture of TiO₂ and Nb₂O₅ powder in liquid slurry - spraying of this slurry to cause the TiO₂-Nb₂O₅ mixed oxide mixture to granulate - plasma spraying of this granulated mixture onto the base body of a sputter target.

IPC 8 full level

C23C 14/34 (2006.01)

CPC (source: EP US)

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Citation (search report)

See references of WO 2007141003A1

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